Conference: 19-23 September 2016

Abstract deadline: 6 May 2016

Notification to authors: 15 July 2016



General information: info@mne2016.org Please register to our MNE Newsletter:

Website: www.mne2016.org

Background

Micro and Nano Engineering is an international conference on micro- and nanofabrication and manufacturing using lithography and related techniques. The conference brings together engineers and scientists from all over the world to discuss recent progress and future trends in the fabrication and application of micro- and nanostructures and devices. Applications in electronics, photonics, electromechanics, environment, life sciences and biology are also discussed. MNE 2016 will be the 42nd conference in a series which started in Cambridge in 1975 and which was held most recently in Berlin (2011), Toulouse (2012), London (2013), Lausanne (2014) and The Hague (2015). In 2016, MNE will return to Austria

Content of the Conference

A. Micro- and Nanopatterning

- Photon lithography
- Mask technology

after 11 years.

- Electron and ion beam lithography
- Soft Lithography: Imprint, micro-contact
- Lithography
- **Directed Self Assembly**
- Tip-based / scanning probe based patterning techniques
- Stencil based patterning
- Novel techniques

- Pattern transfer
- Plasma etching
- E- and ion-beam induced deposition
- 3D nano manufacturing
- 3D microprinting
- Materials for Micro and Nano Inspection and process diagnostics and control
 - (Nano-) metrology
 - Self aligned process

B. Micro- and Nanofabrication C. Micro/Nano Devices and D. Micro- and Nanotech-**Systems**

- MEMS / NEMS
- Micro and nano fluidic systems
- · Meta-materials and their fabrication
- System design
- Micro/Nano devices for physical science
- Data storage
- Packaging technology
- Reliability

nology/engineering for Life Sciences and **Biology**

- Sensing
- Lab-on-Chip
- Organ-on-a-Chip
- Micro nano fluidics for bio/life sciences
- System design and fabrication

As in previous years, all presenters will be kindly asked to publish their contribution in the four special issues to appear after peer-reviewing in the Journal of Microelectronic Engineering.

Conference Venue

MNE 2016 will take place in the Congress Center of Reed Messe Vienna. The architect's groundbreaking vision of a "chameleon-like" conference venue that would be uniquely transformable to meet event organisers' needs became a reality when the Congress Center opened in 2004. The fully integrated partition walls permit an amazing variety of hall layouts. The building complex is also designed for sustainable, resource saving operation. And it goes without saying that the Congress Center is disabled friendly and completely smoke-

The Center has excellent links to the airport, the motorway and rail networks. Just 20 minutes by taxi from Vienna International Airport, it is sandwiched between the pleasure grounds "Prater" and the nearby Danube river - an idyllic setting that is ideal for delegates to unwind between sessions. First-class hotels are within walking distance, in a completely new district that is also home of the new Vienna University of Economics and Business Administration campus. On the other hand, St. Stephen's Cathedral and other attractions in the historic city center are just a few minutes away by underground.

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All submitted abstracts will be evaluated by several members of the International Programme Committee whose names will be listed on the MNE 2016 website.